

an interlayer insulating film formed on the switching elements, the gate signal lines, and the source signal lines; and

pixel electrodes formed over at least the interlayer insulating film and in electrical communication with respective switching elements through contact holes defined in the interlayer insulating film,

wherein the pixel electrodes are comprised of a photosensitive conductive material including at least one coloring agent so that at least some of the pixel electrodes function as both pixel electrodes and color filters.

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Please add the following new claims: /

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9. (New) A liquid crystal display comprising:

a substrate supporting a plurality of address lines in communication with a switching element;

a pixel electrode in electrical communication with the switching element, wherein the pixel electrode is for applying voltage across a liquid crystal layer; and

wherein the pixel electrode comprises a photosensitive conductive material and at least one coloring agent so that the pixel electrode functions as both a pixel electrode and a color filter, and wherein the pixel electrode is photo-patternable due to its photosensitive nature.

10. (New) The liquid crystal display of claim 9, wherein the photosensitive conductive material of the pixel electrode has negative type photosensitivity.

11. (New) A transmissive liquid crystal display including a liquid crystal cell which comprises:

a substrate supporting a plurality of address lines in communication with a switching element;

a transparent pixel electrode in electrical communication with the switching element, wherein the transparent pixel electrode is for applying voltage across a liquid crystal layer;

wherein the transparent pixel electrode comprises a negative type photosensitive conductive material and is photo-patternable due to its photosensitive nature; and

wherein no reflector is provided in the liquid crystal cell under the pixel electrode, so that the liquid crystal display is of the transmissive type.

12. (New) The liquid crystal display of claim 11, wherein the photosensitive conductive material of the pixel electrode has negative type photosensitivity.

13. (New) A method of making an active matrix substrate, the method comprising:

forming switching elements disposed in a shape of a matrix, gate signal lines controlling the switching elements and extending in a first direction, and source signal

lines connected to the switching elements and extending in a second direction perpendicular to the first direction on a front surface of a light permeable substrate;

forming an interlayer insulating film on the switching elements, the gate signal lines, and the source signal lines;

forming on the interlayer insulating film a negative type photosensitive transparent conductive material whose exposed parts are left in a pattern;

performing exposure from a back surface side of the light permeable substrate in order to expose the negative type photosensitive transparent conductive material in a self-alignment fashion by using the gate signal lines and the source signal lines as exposure masks;

developing the negative type photosensitive transparent conductive material so as to obtain pixel electrodes by removing unexposed parts of the negative type photosensitive transparent conductive material.

14. (New) The method of claim 13, wherein the negative type photosensitive conductive material comprises photosensitive resin and conductive particles dispersed in the photosensitive resin.

15. (New) The method of claim 14, wherein the conductive particles comprise indium tin oxide, antimony tin oxide, or zinc oxide.